

## New epitaxy equipment at NanoTecMat technological platform



A silicon-germanium MBE equipment (SG800 from DCA Instruments) was recently installed at NanoTecMat technological platform. This MBE chamber is designed for 200mm wafer size. It is connected to a cluster tool type UHV central distribution chamber allowing future expansion with additional growth chambers, analysis chambers or other processing chambers.

*NanoTecMat, hosted by IM2NP-CNRS/AMU in Marseille, is a micro/nanofabrication technological platform open to academic and industrial partners for research projects or training on silicon based nanostructures*

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